

ABSTRACT OF THE DISCLOSURE

A method for processing objects to be created via photolithography. Each object to be created is defined as a polygon that is fragmented into a number of edge segments that extend around the perimeter of the polygon. At least some of the edge segments have an associated control site where the edge placement error for the edge segment is to be minimal. A smoothing filter is applied to the polygon to identify those control sites that may cause an OPC tool to produce erroneous results. The identified control sites are moved and/or eliminated from the polygon, and polygon and the adjusted control sites are supplied to an OPC tool.

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